

Title (en)

PLASMA GENERATION DEVICE AND PLASMA PROCESSING METHOD

Title (de)

PLASMAERZEUGUNGSVORRICHTUNG UND PLASMAVERARBEITUNGSVERFAHREN

Title (fr)

DISPOSITIF DE GÉNÉRATION DE PLASMA ET PROCÉDÉ DE TRAITEMENT PAR PLASMA

Publication

EP 4050973 A1 20220831 (EN)

Application

EP 19950060 A 20191022

Priority

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Abstract (en)

A plasma generation device includes a device main body in which a reaction chamber for plasmatizing a processing gas is formed, at least one discharge path connected to the reaction chamber, a diffusion chamber connected to the at least one discharge path, and multiple ejection paths that are connected to the diffusion chamber and eject a plasma gas plasmatized in the reaction chamber having a taper surface formed in an opening of at least one ejection path among the multiple ejection paths to the diffusion chamber.

IPC 8 full level

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CPC (source: EP)

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Designated extension state (EPC)

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